**Paper List**

*January – December, 2020*

**E2020-1(F)** Study on CF4/O2 plasma resistance of O-ring elastomer materials
Tetsuya Goto, Shogo Obara, Tomoya Shimizu, Tsuyoshi Inagaki, Yasuyuki Shirai, and Shigetoshi Sugawa
[https://doi.org/10.1116/1.5124533](https://doi.org/10.1116/1.5124533)

Kaname Imokawa, Takayuki Kurashige, Akira Suwa, Daisuke Nakamura, Taizoh Sadoh, Tetsuya Goto, and Hiroshi Ikenoue
[http://doi.org./10.1109/JEDS.2019.2956991](http://doi.org./10.1109/JEDS.2019.2956991)

**E2020-3(C)** An over 120dB dynamic range linear response single exposure CMOS image sensor with two-stage lateral overflow integration trench capacitors
January 28, 2020, San Francisco, U.S.A
Yasuyuki Fujihara, Maasa Murata, Shota Nakayama, Rihito Kuroda, Shigetoshi Sugawa
[https://doi.org/10.2352/ISSN.2470-1173.2020.7.ISS-143](https://doi.org/10.2352/ISSN.2470-1173.2020.7.ISS-143)

**E2020-4(L)** Amorphous titanium-oxide supercapacitors with high capacitance
Mikio Fukuhara, Tomoyuki Kuroda, Fumihiko Hasegawa, Yasuyuki Shirai, Tomoyuki Suwa, Toshiyuki Hashida and Masahiko Nishijima

**E2020-5(F)** Over 100 Million Frames per Second 368 Frames Global Shutter Burst CMOS Image Sensor with Pixel-wise Trench Capacitor Memory Array
Manabu Suzuki, Yuki Sugama, Rihito Kuroda and Shigetoshi Sugawa
[https://doi.org/10.3390/s20041086](https://doi.org/10.3390/s20041086)

**E2020-6(F)** High reliability CoFeB/MgO/CoFeB magnetic tunnel junction fabrication using low-damage ion beam etching
Hyeonwoo Park, Akinobu Teramoto, Jun-ichi Tsushima, Keiichi Hashimoto, Tomoyuki Suwa, Marie Hayashi, Rihito Kuroda, Koji Tsunekawa, and Shigetoshi Sugawa
[https://doi.org/10.35848/1347-4065/ab6cb5](https://doi.org/10.35848/1347-4065/ab6cb5)
A high-precision 1 Ω–10 MΩ range resistance measurement platform for statistical evaluation of emerging memory materials


Takeru Maeda, Yuya Omura, Rihito Kuroda, Akinobu Teramoto, and Shigetoshi Sugawa

http://doi.org/10.35848/1347-4065/ab6d86